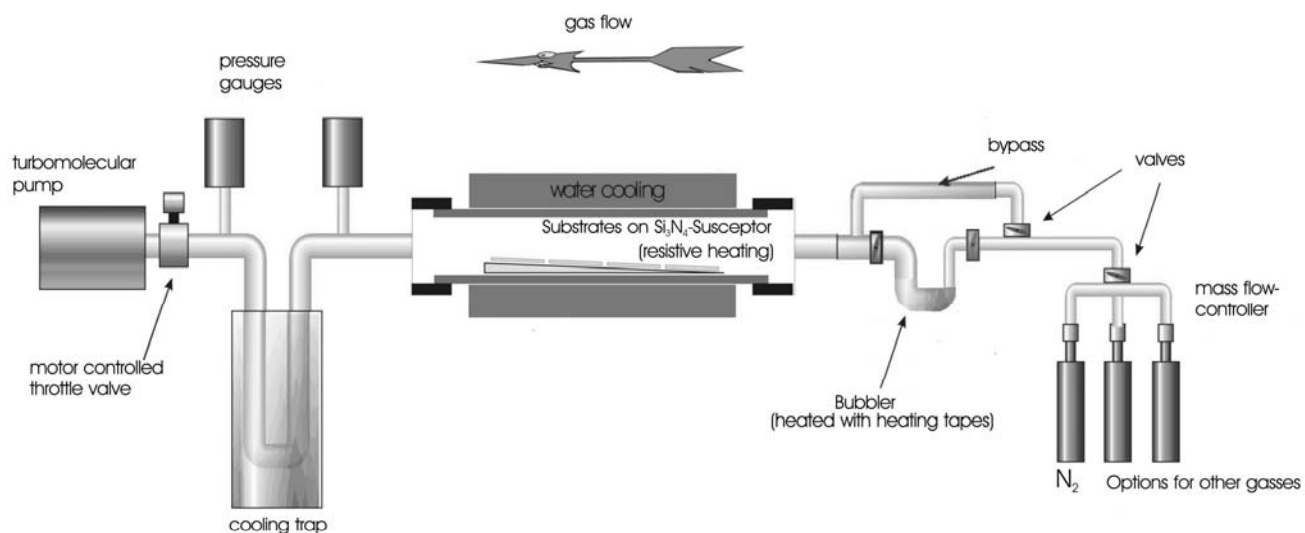


Supplementary Information

Schematic of the MOCVD reactor



Cold wall MOCVD reactor schematic

Film composition from SNMS-Data		
Precursor	no NH_3	NH_3
2	W = 48 %	W = 73 %
	N = 2 %	N = 23 %
	C = 46 %	C = 1,5 %
	O = 4 %	O < 1 %
3	W = 36 %	W = 47 %
	N = 3 %	N = 37 %
	C = 57 %	C = 11 %
	O = 3 %	O = 4 %